

CLAIM CHANGES

(There are no claim changes at this time. Therefore, all claims appear as (Original)).

1. (Original) A semiconductor device comprising:
 - a switching element provided on a surface of a semiconductor layer;
 - a substrate at another surface of the semiconductor layer;
 - a portion of the semiconductor layer located between the switching element and the substrate having an impurity concentration sufficient enough so that a region adjacent to the substrate is not depleted;
 - a defect region provided in a portion of said semiconductor layer includes an entire non depletion layer, wherein the non-depletion layer is not depleted after a switch-off operation;
 - a peak of lattice defect concentration within said non-depletion layer, wherein said lattice defect concentration in the non-depletion layer is sufficient to shorten lifetime of carriers and reduce turn-off time; and
 - a switching control having a current flowing in a thickness direction of the semiconductor layer when said switching element is turned on and off.
2. (Original) A semiconductor device according to claim 1 wherein said defect region does not include said switching element.
3. (Original) A semiconductor device according to claim 1 wherein the life times of carriers in said defect region are shorter than those in other portions.
4. (Original) A semiconductor device according to claim 1 comprising a bipolar transistor with an emitter, a base and a collector thereof laid out in the thickness direction of said semiconductor layer,
 - wherein said switching element is a field-effect transistor which is turned on for injecting carriers to said base of said bipolar transistor.
5. (Original) A semiconductor device according to claim 2 comprising a bipolar transistor with an emitter, a base and a collector thereof laid out in the thickness direction of said semiconductor layer wherein said switching element is a field-effect transistor which is turned on for injecting carriers to said base of said bipolar transistor.

6. (Original) A semiconductor device according to claim 4 wherein said defect region includes an entire portion in said base in close proximity to said emitter which is not depleted after a switch-off operation.
7. (Original) A semiconductor device according to claim 5 wherein said defect region includes an entire portion in said base in close proximity to said emitter which is not depleted after a switch-off operation.
8. (Original) A semiconductor device according to claim 4 wherein said bipolar transistor and said field-effect transistor constitute an insulated-gate bipolar transistor (IGBT).
9. (Original) A semiconductor device according to claim 5 wherein said bipolar transistor and said field-effect transistor constitute an insulated-gate bipolar transistor (IGBT).
10. (Original) A semiconductor device according to claim 6 wherein said bipolar transistor and said field-effect transistor constitute an insulated-gate bipolar transistor (IGBT).
11. (Original) A semiconductor device according to claim 7 wherein said bipolar transistor and said field-effect transistor constitute an insulated-gate bipolar transistor (IGBT).